

## **Problem set 1**

**Deadline 05.03.2025**

*Use the material from*

*V.F. Gantmakher "Electrons and Disorder in Solids", Chapter 1*

*A.A. Abrikosov "Fundamentals of Theory of Metals", Chapter 3*

1. Derive the expression for electronic diffusion coefficient  $D$  in a metal (consider two- and three-dimensional cases). Derive the Einstein relation between  $D$  and electrical conductivity. Estimate resistivity of a typical metal (take Cu or Au as an example) assuming the mean free path  $\sim 100$  nm.
2. Plot schematically temperature dependence of electrical resistivity for a typical metal and discuss its main features in terms of various mechanisms of electronic scattering (impurities, electron-electron and electron-phonon interaction).

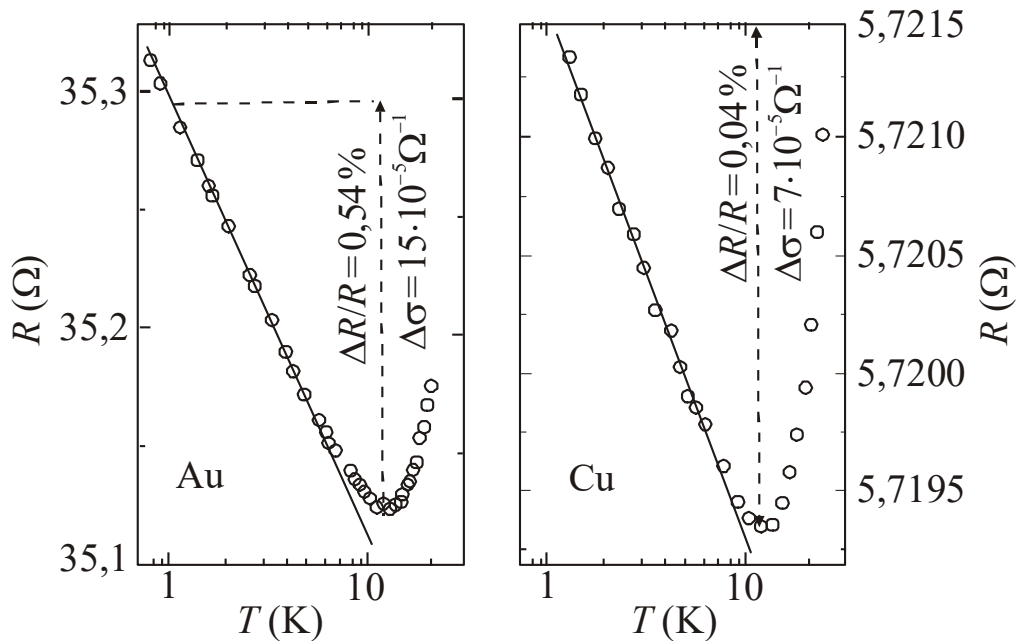
## Problem set 2

Deadline 17.03.2025

1) Using the weak localization theory, explain the main features of the experimental data shown below

Au – S.I. Dorozhkin, *et. al.*, JETP Lett. **36**, 15 (1982)

Cu – L. Van der Dreis *et. al.*, PRL **46**, 565 (1981)



2) Using the above data, estimate the electronic mean free path  $l$  and the phase breaking length  $L_\phi$  in Au and Cu at  $T = 2$  K.

3) For both films, plot qualitatively the dependence of the resistance on magnetic field at  $T=2$ K. How it depends on a magnetic field direction ?

4) Prove that the condition  $\Omega\tau \ll l$  is fulfilled, where  $\Omega$  is the cyclotron frequency, corresponding to the magnetic field  $B_\phi$ .

5) Discuss possible ways of experimental determination of the phase breaking length  $L_\phi$

### Problem set 3

**Deadline 10.04.2025**

1. Estimate a Coulomb gap in a material with permittivity  $\kappa=10$ 
  - (a) in 3D regime with carrier concentration  $10^{16} \text{ cm}^{-3}$
  - (b) in 2D regime with carrier concentration  $10^{12} \text{ cm}^{-2}$ .
2. Consider thin film with thickness 100 nm, permittivity  $\kappa=10$ , concentration of carriers  $10^{18} \text{ cm}^{-3}$  and effective mass  $0.1m_e$ . Estimate crossover temperature when electronic hopping behaviour changes from three-dimensional to two-dimensional regime i.e. when the resistivity behaviour changes from  $\rho = \rho_0 \exp(T_M / T)^{1/4}$  to  $\rho = \rho_0 \exp(T_M / T)^{1/3}$ .
3. Derive the expression (or explain the main steps in its derivation) for the screening length given by Eq.5.42 in Gantmakher's book.  
Hint: the discussion for two dimensions can be found e.g. on pp.73-74 in Datta's textbook "Electronic transport in mesoscopic systems".
4. Show that dimensionless conductance  $y$  defined by Eq.6.1 in Gantmakher's book is the ratio of Thouless energy and mean level spacing for any sample dimensionality. Discuss the physical meaning of Thouless energy.